

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) An apparatus for treating a workpiece with a plasma, comprising:
 - a chamber having a processing space and a wall;
 - a gas supply port in said chamber for introducing a process gas into said processing space;
 - a workpiece holding portion positioned in said processing space and configured for holding the workpiece;
 - a plasma excitation source operable for exciting the process gas in said processing space to generate a plasma;
 - a powered electrode electrically connected to said plasma excitation source and said workpiece-holding portion;
 - a vacuum port in said chamber for evacuating said processing space, ~~said vacuum port being located in said chamber below said powered electrode, and said vacuum port having a centerline oriented substantially perpendicular to said powered electrode~~; and
 - a vacuum distribution baffle positioned ~~below said powered electrode and above said vacuum port between said vacuum port and said workpiece holding portion~~ for uniformly dispersing process gas across said powered electrode, said vacuum distribution baffle operating for electrically shielding said powered electrode from said chamber and for preventing plasma

generation in a portion of said processing space between said vacuum distribution baffle and said vacuum port; and

an electrical feedthrough extending through said wall of said chamber and electrically coupled with said powered electrode, said electrical feedthrough extending through said vacuum distribution baffle.

2. (Previously Presented) The apparatus of claim 1, wherein said powered electrode is part of an assembly which includes said workpiece holding portion.
3. (Previously Presented) The apparatus of claim 1, wherein said workpiece holding portion includes first and second side rails that are adjustable in width to accommodate workpieces of different widths positioned therebetween.
4. (Previously Presented) The apparatus of claim 1, wherein the chamber further comprises a lid, a lower chamber portion, and a sealing member between said lid and said lower chamber portion, said lid movable relative to said lower chamber portion between an open position and a closed position in which said sealing member forms a seal between said lid and said lower chamber portion, said lid being connected to said lower chamber portion by a hinge having a slotted opening and a hinge pin positioned in said slotted opening, said slotted opening oriented such that said lid moves vertically relative to said lower chamber portion for compressing said sealing member when said lid is in the closed position and said processing space is evacuated through said vacuum port

5. (Original) The apparatus of claim 1 further comprising:

a ground electrode positioned on an opposite side of said workpiece holding portion relative to said powered electrode.

6. (Previously Presented) The apparatus of claim 5, wherein said powered electrode and said ground electrode are approximately equidistant from said workpiece holding portion, said electrodes producing an electric field substantially perpendicular to the workpiece when said workpiece is held in said workpiece holding portion.

7. (Previously Presented) The apparatus of claim 6, wherein said chamber includes a lid movable between open and closed positions for accessing said workpiece holding portion, said lid further comprising said ground electrode.

8. (Cancelled)

9. (Previously Presented) The apparatus of claim 1, wherein said chamber includes a lid movable between open and closed positions for accessing said workpiece holding portion, and said gas supply port is positioned in said lid for introducing the process gas to said processing space.

10. (Previously Presented) The apparatus of claim 9, wherein said lid includes an interior surface facing said workpiece holding portion of said processing space when said lid is in said closed position, and said gas supply port further comprises a gas distribution space within said lid and an array of apertures on said interior surface configured to uniformly distribute the process gas from said gas distribution space onto the workpiece.

11. (Cancelled)

12. (Currently Amended) The apparatus of claim [[11]] 1, wherein said chamber further comprises a lower chamber portion, a lid movable relative to said lower chamber portion between open and closed positions for accessing said workpiece holding portion, and a sealing member between said lid and said lower chamber portion, said sealing member [[is]] being electrically conductive so that said access member lid and said lower chamber [[base]] portion are in electrical continuity when said access member lid is in said closed position.

13-48. (Cancelled)

49. (Previously Presented) The apparatus of claim 1 wherein said vacuum distribution baffle includes a plate having a plurality of orifices that permit the process gas to flow from said gas supply port to said vacuum port.

50. (Previously Presented) The apparatus of claim 49 wherein said chamber base, said plate is positioned between said chamber base and said powered electrode, said powered electrode includes a perimeter, and said vacuum port is symmetrically positioned in said chamber base relative to said perimeter.

51. (Cancelled)

52. (Currently Amended) The apparatus of claim [[1]] 54 wherein said powered electrode is located below said gas supply port.

53. (Currently Amended) The apparatus of claim [[1]] 54 wherein said vacuum port is centrally located in said chamber below said powered electrode.

54. (New) The apparatus of claim 1 wherein said vacuum port is located in said chamber below said powered electrode, and said vacuum port has a centerline oriented substantially perpendicular to said powered electrode.

55. (New) The apparatus of claim 1 wherein said vacuum distribution baffle is located below said powered electrode and above said vacuum port for uniformly dispersing process gas across said powered electrode.

56. (New) The apparatus of claim 55 wherein said vacuum port is located in said chamber below said powered electrode, and said vacuum port has a centerline oriented substantially perpendicular to said powered electrode.